

PATENT

In re application of: DAVID L O'MEARA, CORY WAJDA, TSUYOSHI TAKAHASHI,
ALESSANDRO CALLIGARI, KRISTEN SCHEER, SUFI ZAFAR, and
PAUL JAMISON

Commissioner for Patents
P.O. Box 1450
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BIBLIOGRAPHIC DATA

Sixth applicant: SUFI ZAFAR
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Residence: Briarcliff Manor, NY 10510

Seventh applicant: PAUL JAMISON
Citizenship: USA
Residence: Hopewell Junction, NY 12533

2. Correspondence information

Correspondence for this application should be addressed as follows:

Customer No.: 00909

3. Application information

Title of Invention: INTERFACIAL OXIDATION PROCESS FOR HIGH-K GATE
DIELECTRIC PROCESS INTEGRATION

Docket number assigned to this application: 071469-0305306

Suggested Classification: Class:

Subclass:

Technology Center to which subject matter is assigned:

Total number of drawing sheets: 10

Type of application:

Utility

Application is to be published. Suggested drawing figure for publication:

Secrecy order under § 5.2:

This application does not disclose subject matter of an application which is under a secrecy order pursuant to § 5.2.

4. Representative information

The following have a power of attorney or authorization of agent in this application:

Customer No.: 00909

5. Assignee information

The assignee(s) of this application is/are:

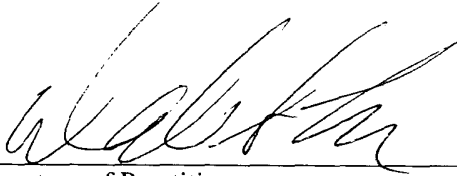
Tokyo Electron Limited
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Extent of interest of assignee in application: 50%

International Business Machines Corporation
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Armonk, NY 10504
Extent of interest of assignee in application: 50%

Date: September 16, 2003

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